

ABSTRACT

COMPOSITION FOR FORMING FINE PATTERN
AND

5 METHOD FOR FORMING FINE PATTERN USING THE SAME

The present invention provides a resist pattern-forming composition capable of forming a resist pattern excellent in etching resistance. The invention also provides a resist pattern formation method using that composition. The composition comprises pure water and a water-soluble resin having aromatic group-containing substituents in its side chain. The composition also contains a free acid or an acid group combined with the water-soluble resin.

Nil